Claims

1. Apparatus for holding a planar substrate, having a support that forms a supporting surface for the substrate, which has at least one supporting surface recess provided in the region of the supporting surface for the substrate, and having at least one holder connected with this supporting surface recess, in terms of flow, for fastening the substrate onto the apparatus, using a partial vacuum generated between the support and the substrate, wherein the support has at least one support recess having an elastic seal configured to be moveable from a position projecting beyond the edge of the support recess into a position agreeing with the edge support of the support recess, the elastic seal working together with the supporting surface recess to draw the substrate against the support over a full area of the substrate, by suction, wherein the elastic seal runs conically in cross-section, is free in a tilting direction, has two equal bending shanks in order to allow a tilting movement of the elastic seal, and is structured as a tubular seal.

2. Apparatus according to claim 1, wherein the elastic seal is configured to be passively moved by the substrate.

3. Apparatus according to claim 1, wherein the supporting surface recesses are disposed distributed over the support.

4. Apparatus according to claim 1, wherein the support recess forms a closed contour progression.

5. Apparatus according to claim 1, wherein the elastic seal essentially surrounds the supporting surface recess.

6. Apparatus according to claim 1, wherein the support recess divides the supporting surface into two supporting surface portions.

7. Apparatus according to claim 6, wherein the support recess follows an edge-side supporting surface portion.

8. Apparatus according to claim 1, wherein the support recess and the supporting surface recess run concentrically.

9. Apparatus according to claim 1, wherein the elastic seal is connected with the bottom of the support recess with a firm bond.

10. Apparatus according to claim 1, wherein the support has multiple support recesses having elastic seals, which divide the support into multiple supporting surface portions, which support recesses run offset form one another.

11. Apparatus according to claim 10, wherein the multiple supporting surface portions each have a supporting surface recess, and wherein the supporting recess of a first supporting surface portion is connected with the holder, in terms of flow, separately from the supporting surface recesses of the other supporting surface portions.

12. Apparatus according to claim 1, wherein the elastic seal is configured to be moveable from a position projecting beyond the edge of the

support recess into a position pulled back in relation to the edge of the support recess.

13. Apparatus according to claim 1, wherein the elastic seal completely surrounds the supporting surface recess.

14. Apparatus according to claim 1, wherein the substrate is configured to support a wafer and/or eWLB.

15. Apparatus according to claim 10, wherein the support recesses run radially offset from one another.